

Near-field Imaging and Nano-FTIR Spectroscopy using Synchrotron Radiation from the Metrology Light Source (MLS)

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Intensity

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Scan2

Scan3

Scan4

825

850

run; single peak maximum at 927cm⁻¹.

Frequency (1/cm)

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Introduction: Near-field optical microscopy (SNOM) is a versatile technique for imaging of nanoscale structures with a spatial resolution significantly below the diffraction limit. IR-SNOM measurements performed with laser sources provide spatially resolved information about the optical properties of the sample at discrete wavelengths. However, the spectra acquisition is time consuming since it requires repeated measurements at different wavelengths, the number (hence spectral resolution) of which is also limited. Thus near-field FTIR spectroscopy using broadband radiation such as from thermal sources or electron storage rings is desireable.

In this work we couple a scattering-type IR-SNOM to the IR-beamline at the MLS [1]. Compared to conventional thermal sources the use of synchrotron radiation provides several major advantages such as (i) a higher brilliance, (ii) pulsed radiation in the ps range, and (iii) polarized radiation. In the following we analyse graphitized 6H-SiC to demonstrate high-resolution imaging and nano-FTIR spectroscopy by using a broadband synchrotron radiation source, and compare to laser based near-field imaging at different wavelengths. We find significant differences in the contrast mechanisms and indications of strong plasmon reflections at SiC step-edges.

Samples:

- E3: 6H-SiC (0001) oriented (Si-face), vanadium doped, semi-insulating
- G033, G068: H-etching of substrates like E3 [2] resulting in step -bunching; subsequently graphitized [3] (thermal decomposition), resulting in 60% monolayer coverage (n-type with densities $>10^{12}$ cm⁻²), as well as some bi-layer formation
- D01: 6H-SiC, undoped



Fig 1: AFM image showing topography of G033 sample





Nano FTIR Measurements, using 4th harmonic:

- Enhanced emission of graphene wrt. pure SiC surface due to plasmon -phonon coupling [4]. Note opposite effect in laser imaging, see Fig. 7
- Spectra vary for doped and undoped SiC samples, Fig. 8
- Weak influence of graphitization (pure SiC region on G033) wrt. starting material (E3), see Fig. 8
- Almost no difference between bilayer and monolayer graphene, Fig. 8



3.0

Fig 2: 4th harmonic signal intensity s₄ corresponding to Fig 1 using broadband IR excitation; Location A and B corresponds to SiC covered by mono- and bilayers, respectively. C shows the uncovered SiC surface.

750 775 800 Fig 6: FTIR spectrum of undoped SiC sample D01; recorded in a different measurement



G033 location C/E3

Fig 8: Intensity ratios between different spectra; black squares show plasmon enhanced SiC phonon peak towards higher frequencies; the variation D01/E3 (triangles) comes from the peakshift of the doped SiC (E3) towards a smaller frequency of 927cm⁻¹

Laser based near-field imaging

Imaging of G068 sample as function of laser wavelength using 4th harmonic signal intensity s_4

- Depending on wavelength uncovered SiC (marked in Fig. 9), graphene or stepedges dominate
- Contrast inverses compared to broadband imaging (see also Fig. 7)



Enhanced emission at SiC step edges, as well as signal fluctuations along the edges, as recently observed by Chen et al. [5] on quasi-freestanding monolayer graphene; in contrast, in G033/G068 the buffer layer was not decoupled;

875 900 925 950 975

Note: over graphene regions SNOM signal remains constant for all excitation wavelengths;



Fig 9 Corresponding AFM (a) and laser based SNOM images (b-f), recorded at different laser wavelengths; Laser power measured at interferometer entrance is indicated;

References:

[1] P. Hermann *et al.*, Optics Express **21**, 2913 (2013) [2] J. Robinson *et al.*, ACS Nano **4**, 153 (2009)

[3] A. van Bommel *et al.*, Surface Science **48**, 463 (1975) [4] Z. Fei *et al.*, Nano Letters **11**, 4701 (2011) [5] J. Chen *et al.*, Nano Letters **13**, 6210 (2013)



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